

United States Patent and Trademark Office



APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
09/696,232	10/26/2000	Mitsuru Ishikawa	07553.0017	5127
22852	7590 02/27/2004		EXAMINER	
FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER LLP			OLSEN, ALLAN W	
			ART UNIT	PAPER NUMBER
WASHINGTO	WASHINGTON, DC 20005		1763	·

DATE MAILED: 02/27/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

- F		Application No.	Applicant(s)				
		09/696,232	ISHIKAWA ET AL.				
Office Action Summary		Examiner	Art Unit				
		Allan W Olsen	1763				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address							
Period fo		ALC CET TO EXPIDE 2 MON	TU(S) EDOM				
THE N - Exten after S - If the - If NO - Failur - Any re	DRTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. sions of time may be available under the provisions of 37 CFR 1.1: SIX (6) MONTHS from the mailing date of this communication. period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period to treply within the set or extended period for reply will, by statute apply received by the Office later than three months after the mailing d patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply by within the statutory minimum of thirty (30 will apply and will expire SIX (6) MONTHS cause the application to become ABAND	oe timely filed) days will be considered timely. from the mailing date of this communication. ONED (35 U.S.C. § 133).				
Status		2					
1)[Responsive to communication(s) filed on <u>02 L</u>						
2a)	,—	is action is non-final.					
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.							
Dispositi	on of Claims						
4)🖂	Claim(s) 1-5,13 and 14 is/are pending in the a	pplication.					
•	4a) Of the above claim(s) is/are withdraw	wn from consideration.					
5)	Claim(s) is/are allowed.						
6)⊠	6)⊠ Claim(s) <u>1-5,13 and 14</u> is/are rejected.						
7)	Claim(s) is/are objected to.						
•	Claim(s) are subject to restriction and/o	r election requirement.					
• •	on Papers						
9) The specification is objected to by the Examiner.							
10) ☐ The drawing(s) filed on 18 March 2003 is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.							
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
11) The proposed drawing correction filed on is: a) □ approved b) □ disapproved by the Examiner. If approved, corrected drawings are required in reply to this Office action.							
12) The oath or declaration is objected to by the Examiner.							
Priority under 35 U.S.C. §§ 119 and 120 13)⊠ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).							
•	All b) Some * c) None of:	r priority under do d.d.d. 3 v	(4)				
ر م ا	1.⊠ Certified copies of the priority document	s have been received.					
	Certified copies of the priority document		ication No.				
	3. Copies of the certified copies of the prior						
, * S	application from the International Bu See the attached detailed Office action for a list	reau (PCT Rule 17.2(a)).					
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).							
)						
Attachmen	t(s)						
2) Notic	e of References Cited (PTO-892) se of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449) Paper No(s)	5) Notice of Infor	nmary (PTO-413) Paper No(s) rmal Patent Application (PTO-152)				

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DETAILED ACTION

Continued Examination Under 37 CFR 1.114

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on December 2, 2003 has been entered.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-4, 13 and 14 are rejected under 35 U.S.C. 102(b) as being anticipated by US Patent 5,658425 issued to Halman et al. (hereinafter, Halman). Halman teaches using a plasma comprising CF₄, Ar and N₂ to etch a multi-layered oxide. Halman teaches the multilayered oxide may comprise a BPSG (Halman's layer 5) with an overlying layer of TEOS (Halman's layer 8) which corresponds to Applicant's claimed organic film containing Si. Halman teaches the multilayered oxide may also comprise an overlying layer of a planarizing spin-on-glass. Halman provides examples in which the amount of N₂ is less than the amount of CF₄, however, Halman teaches that an unlimited amount of N₂ may be used. See: abstract; column 4, lines 18-21, 35-41 and 50-53; and column 5, lines 8-12.

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Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claim 5 is rejected under 35 U.S.C. 103(a) as being unpatentable over Halman as applied to claim 1 above, and further in view of US Patent 5,721,156 issued to Matsuura (hereinafter, Matsuura).

Halman does not teach that the Si-containing organic layer is a polysiloxane.

Matsuura teaches forming a TEOS derived polymeric layer. Matsuura teaches that a polysiloxane can be used in place of the TEOS layer.

It would have been obvious to one skilled in the art to use a polysiloxane because in semiconductor fabrication processes TEOS layers are generally polymeric layers that are derived from TEOS and these TEOS derived polymeric layers typically comprise polysiloxane. Alternatively, it would have been obvious to use a polysiloxane because Matsurra teaches that a TEOS derived layer and a polysiloxane layer are functionally equivalent.

Response to Arguments

Applicant's arguments have been considered but are moot in view of the new grounds of rejection.

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Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

US patent 5,835,987 notes that the dielectric constant of TEOS is 3.0.

US Patent 5,262,358 demonstrates that TEOS is a polysiloxane precursor.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Allan Olsen whose telephone number is 571-272-1441. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Greg Mills, can be reached on 571-272-1439.

The fax number for TC1700 is 703-872-9306 (non-after finals and after-final).

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the Group receptionist whose telephone number is (571) 272-1300. Ma Olse

Allan Olsen, Ph.D. February 19, 2004